

6 an end effector attached to the distalmost link and being rotatable about an  
7 end effector axis;

8 a motor connected to rotate the end effector about the end effector axis to  
9 thereby provide a yaw motion; and

cont. 10 means for monitoring and controlling the yaw motion such that the end  
11 effector axis can be moved in a straight line which is not restricted to the radial direction,  
12 and wherein the means for monitoring and controlling the yaw motion moves the end  
13 effector in a straight line and maintains a constant orientation of the end effector.

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1 <sup>9.</sup>~~31.~~ (Amended) A robotic arm structure providing  $\theta$  motion and R motion about  
2 a primary axis, the arm structure comprising:

3 an end effector for transporting semiconductor substrates attached to the arm  
4 structure and being rotatable about an end effector axis;

5 a first motor connected to rotate the end effector about the end effector axis  
6 to provide a yaw motion;

7 a second motor connected to rotate the end effector to provide a roll motion  
8 of the end effector; and

9 means for monitoring and controlling the yaw and roll motions;

10 wherein the end effector has at least two hands such that the second motor  
11 rolls a first hand and a third motor rolls a second hand.

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1 <sup>11</sup>~~38.~~ (Amended) A robotic arm structure providing  $\theta$  motion and R motion about  
2 a primary axis, the arm structure comprising:

3 an end effector for transporting semiconductor substrates attached to the arm  
4 structure and being rotatable about an end effector axis;

5 a first motor connected to rotate the end effector about the end effector axis  
6 to provide a yaw motion;

7 a second motor connected to rotate the end effector to provide a roll motion  
8 of the end effector;  
9 a third motor connected to rotate the end effector to provide a pitch motion  
10 of the end effector; and  
11 means for monitoring and controlling the yaw, roll, and pitch motion;  
12 wherein the end effector has at least two hands.

cont.  
D13

14.  
39. (Amended) A robotic arm structure providing  $\theta$  motion and R motion about  
2 a primary axis, the arm structure comprising:  
3 an end effector for transporting semiconductor substrates attached to the arm  
4 structure and being rotatable about an end effector axis;  
5 a first motor connected to rotate the end effector about the end effector  
6 access to provide a yaw motion;  
7 a second motor connected to rotate the end effector to provide a pitch motion  
8 of the end effector; and  
9 means for monitoring and controlling the yaw and pitch motions;  
10 wherein the end effector has at least two hands such that the second motor  
11 itches a first hand and a third motor itches a second hand.

D4

In Claim 45, line 1, delete "Claim 44," and insert --Claim 31,--.

**REMARKS**

Reconsideration and allowance of the above-identified application are respectfully requested. Claims 1-7, 31, 35, 39, 45-47, and 49 are currently pending.

**Rejections under 35 U.S.C. §103:**

Claims 1-3, 49 and 50 have been rejected under 35 U.S.C. §103 as being unpatentable over Tabata et al. in view of Ueyama, et al.